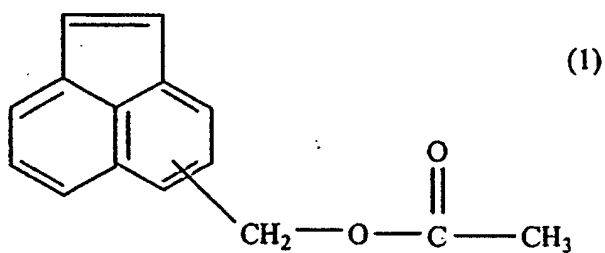


Amendments to the Claims:

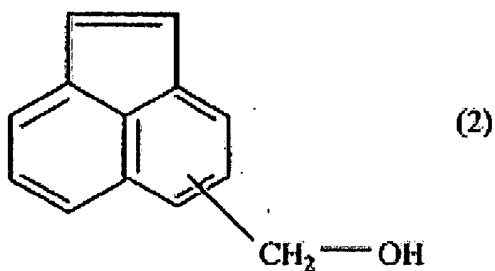
This listing of claims will replace all prior versions and listings of claims in the application.

Listing of Claims:

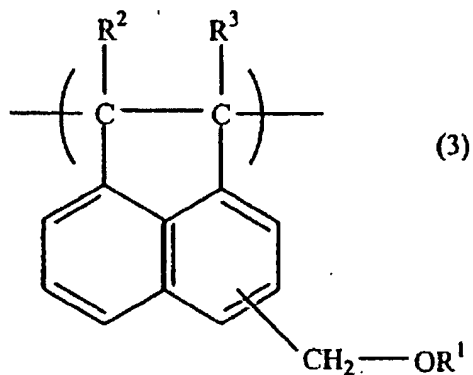
1. (Previously presented) Acetoxymethylenaphthylene of the following formula (1)



2. (Previously presented) Hydroxymethylenaphthylene of the following formula (2)



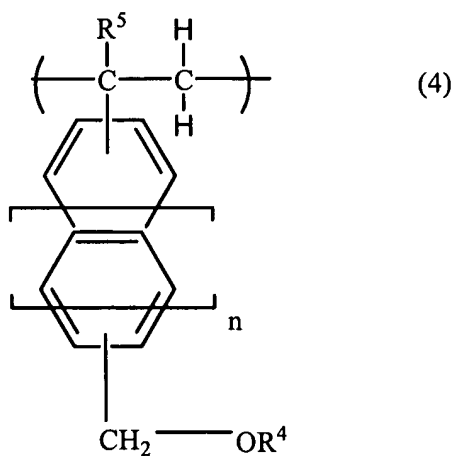
3. (Original) A polymer containing a structural unit of the following formula (3),



wherein R¹ is a hydrogen atom and R² and R³ individually represent a monovalent atom or a monovalent organic group, the polymer having a polystyrene-reduced weight average molecular weight determined by gel permeation chromatography (GPC) in the range of 500 to 10,000.

4. (Original) An antireflection film-forming composition comprising the polymer of Claim 3 and a solvent.

5. (Currently Amended) An antireflection film-forming composition comprising, a polymer having a structural unit of the following formula (4)

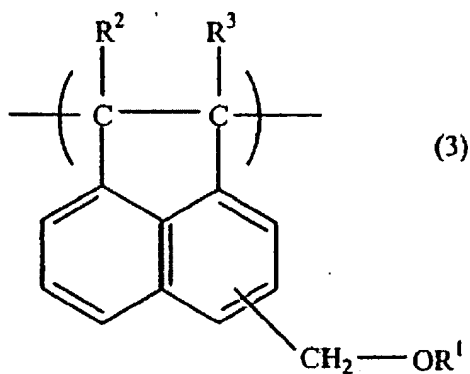


wherein R^4 is a monovalent organic group selected from the group consisting of a phenyl group, an alkyl group, an alkenyl group, an acyl group, and a group in which one or more hydrogen atoms of a phenyl group, an alkyl group, an alkenyl group, or an acyl group are replaced by one or more of the same or different substituents selected from the group consisting of a halogen atom, a hydroxyl group, a mercapto group, a nitro group and a sulfonic acid group, R^5 is a monovalent atom or a monovalent organic group, and n is [[0 or]] 1, and

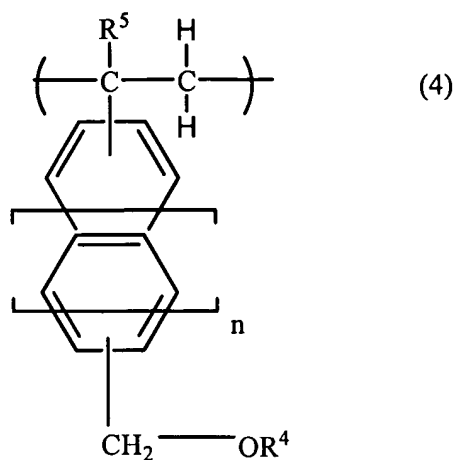
a solvent.

6. (Previously Presented) An antireflection film-forming composition comprising,

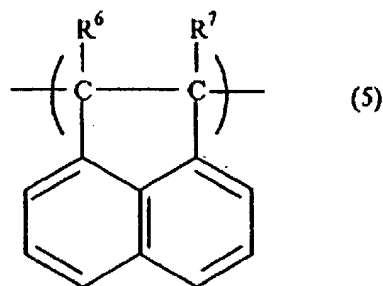
at least one polymer selected from the group consisting of: a polymer having a structural unit of the following formula (3)



wherein R^1 is a hydrogen atom and R^2 and R^3 individually represent a monovalent atom or a monovalent organic group and a structural unit of the following formula (4)



wherein R^4 is a hydrogen atom or a monovalent organic group, R^5 is a monovalent atom or a monovalent organic group, and n is 0 or 1; a polymer having a structural unit of the formula (3) and a structural unit of the following formula (5)



wherein R^6 and R^7 individually represent a monovalent atom or a monovalent organic group; and a polymer having a structural unit of the formula (4) and a structural unit of the formula (5); and
a solvent.

7. (Original) The antireflection film-forming composition according to Claim 4, further comprising an acid generator.

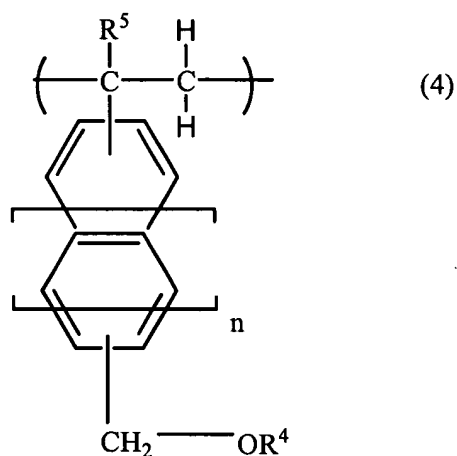
8. (Original) The antireflection film-forming composition according to Claim 5, further comprising an acid generator.

9. (Original) The antireflection film-forming composition according to Claim 6, further comprising an acid generator.

10. (Canceled).

11. (Previously presented) An antireflection film-forming composition comprising:

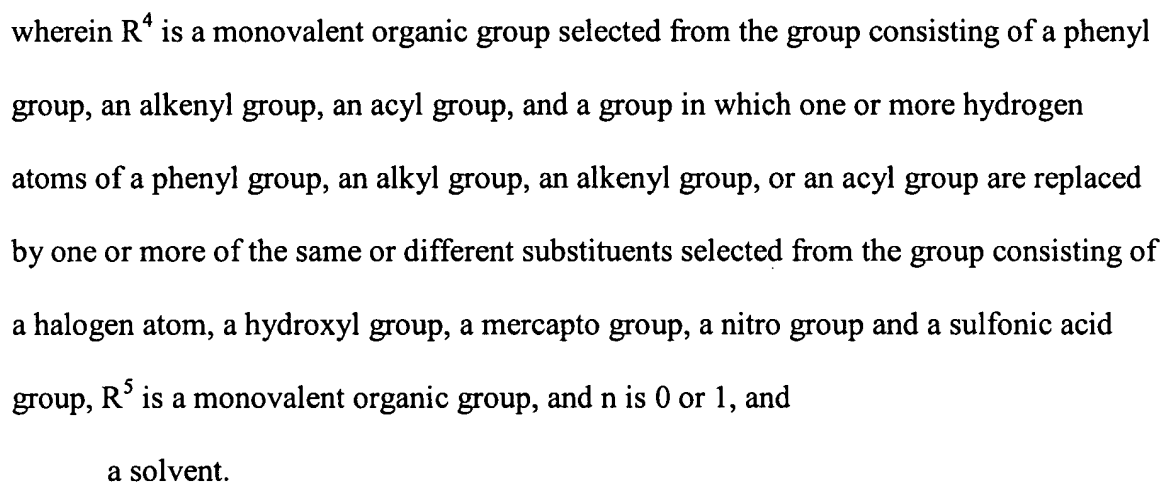
a polymer having a structural unit of the following formula (4);



wherein R^4 is a hydrogen atom or a monovalent organic group and R^5 is a monovalent atom or a monovalent organic group; and

a solvent.

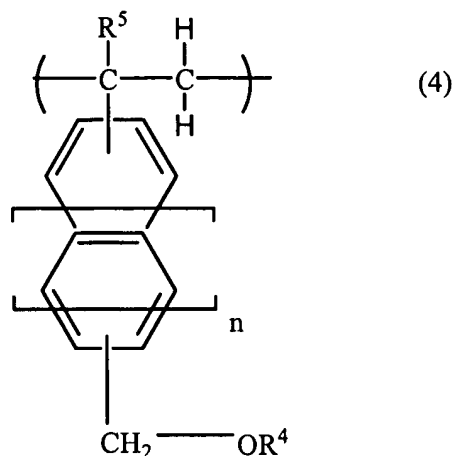
13. (New) An antireflection film-forming composition comprising,
a polymer having a structural unit of the following formula (4)



14. (New) The antireflection film-forming composition according to Claim 13, further comprising an acid generator.

15. (New) An antireflection film-forming composition comprising,

a polymer having a structural unit of the following formula (4)



wherein R⁴ is a monovalent organic group selected from the group consisting of an alkenyl group and a group in which one or more hydrogen atoms of a phenyl group, an alkyl group, an alkenyl group, or an acyl group are replaced by one or more of the same or different substituents selected from the group consisting of a halogen atom, a hydroxyl group, a mercapto group, a nitro group and a sulfonic acid group, R⁵ is a monovalent atom or a monovalent organic group, and n is 0 or 1, and

a solvent.

16. (New) The antireflection film-forming composition according to Claim 15, further comprising an acid generator.